

* * * * * Welcome to STN International * * * * *

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 NEWS 2 "Ask CAS" for self-help around the clock
 NEWS 3 SEP 09 CA/CAPLUS records now contain indexing from 1907 to the present
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 NEWS 5 AUG 13 Field Availability (/FA) field enhanced in BEILSTEIN
 NEWS 6 AUG 18 Data available for download as a PDF in RDISCLOSURE
 NEWS 7 AUG 18 Simultaneous left and right truncation added to PASCAL
 NEWS 8 AUG 18 FROSTI and KOSMET enhanced with Simultaneous Left and Right Truncation
 NEWS 9 AUG 18 Simultaneous left and right truncation added to ANABSTR
 NEWS 10 SEP 22 DIPPR file reloaded
 NEWS 11 SEP 25 INPADOC: Legal Status data to be reloaded
 NEWS 12 SEP 29 DISSABS now available on STN
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NEWS EXPRESS OCTOBER 01 CURRENT WINDOWS VERSION IS V6.01a, CURRENT MACINTOSH VERSION IS V6.0b(ENG) AND V6.0Jb(JP), AND CURRENT DISCOVER FILE IS DATED 23 SEPTEMBER 2003

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FILE 'HOME' ENTERED AT 06:47:29 ON 13 OCT 2003

=> file inspec

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'INSPEC' ENTERED AT 06:47:39 ON 13 OCT 2003

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FILE LAST UPDATED: 13 OCT 2003 <20031013/UP>
 FILE COVERS 1969 TO DATE.

<<< SIMULTANEOUS LEFT AND RIGHT TRUNCATION AVAILABLE IN THE BASIC INDEX >>>

=> a phase shift mask

713679 PHASE

147036 SHIFT

21527 MASK

L1 516 PHASE SHIFT MASK
 (PHASE(W) SHIFT(W) MASK)

=> a exposure optical system

61904 EXPOSURE

668960 OPTICAL
1595550 SYSTEM
L2 1 EXPOSURE OPTICAL SYSTEM
(EXPOSURE(W)OPTICAL(W)SYSTEM)

=> & 12

L2 ANSWER 1 OF 1 INSPEC (C) 2003 IEE on STN

Full Text

AN 2001:6804707 INSPEC DN B2001-02-2550G-151
TI Influence of electron density distribution at the electron source in a projection exposure system.
AU Kotera, M.; Sakai, M. (Osaka Inst. of Technol., Japan); Shimizu, I.; Tomo, Y.; Yoshida, A.; Kojima, Y.; Yamabe, M.
SO Digest of Papers Microprocesses and Nanotechnology 2000. 2000 International Microprocesses and Nanotechnology Conference (IEEE Cat. No.00EX387)
Tokyo, Japan: Japan Soc. Appl. Phys, 2000. p.140-1 of xxviii+306 pp. 0 refs.
Conference: Tokyo, Japan, 11-13 July 2000
Sponsor(s): Japan Soc. Appl. Phys.; IEEE Electron Device Soc.; American Vacuum Soc.; Assoc. Super-Adv. Electron. Technol.; IEE of Japan; IEICE; Japanese Soc. Synchrotron Radiation Res.; Japanese Soc. Electron Microscopy; Surface Sci. Soc. Japan; Vacuum Soc. Japan
ISBN: 4-89114-004-6
DT Conference Article
TC Theoretical
CY Japan
LA English

=> & excavation

L3 871 EXCAVATION

=> & 11 and 12

L4 0 L1 AND L2

=> & 11 and 13

L5 0 L1 AND L3

=> & resist pattern

12602 RESIST
182954 PATTERN
L6 424 RESIST PATTERN
(RESIST(W)PATTERN)

=> & 11 and 16

L7 7 L1 AND L6

=> & 17 1-7

L7 ANSWER 1 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 2003:7717431 INSPEC DN B2003-10-2550G-142
TI Preliminary study of 65 nm node alternating **phase-shift mask** fabrication.
AU Hosono, K.; Ishiwata, N.; Asai, S.; Maruyama, H.; Miyahara, Y. (Fujitsu Ltd., Tokyo, Japan); Sanki, S.; Yamashita, Y.; Hotta, Y.; Furukawa, T.; Naitou, M.; Miyashita, H.; Noguchi, S.
SO Proceedings of the SPIE - The International Society for Optical Engineering (2002) vol.4889, p.1273-80. 3 refs.
Published by: SPIE-Int. Soc. Opt. Eng
Price: CCCC 0277-786X/02/\$15.00

CODEN: PSISDG ISSN: 0277-786X
 SICI: 0277-786X(2002)4889L:1273:PSNA;1-Y
 Conference: 22nd Annual BACUS Symposium on Photomask Technology. Monterey, CA, USA, 1-4 Oct 2002
 Sponsor(s): SPIE

DT Conference Article; Journal
 TC Experimental
 CY United States
 LA English

L7 ANSWER 2 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 1998:5803277 INSPEC DN B9802-2550G-201
 TI Optical proximity correction of alternating phase-shift masks for 0.18 μ m KrF lithography.
 AU Yasuzato, T.; Ishida, S. (ULSI Device Dev. Lab., NEC Corp., Sagamihara, Japan); Shioiri, S.; Tanabe, H.; Kasama, K.
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1997) vol.3051, p.751-62. 5 refs.
 Published by: SPIE-Int. Soc. Opt. Eng
 Price: CCCC 0277-786X/97/\$10.00
 CODEN: PSISDG ISSN: 0277-786X
 SICI: 0277-786X(1997)3051L:751:OPCA;1-0
 Conference: Optical Microlithography X. Santa Clara, CA, USA, 12-14 March 1997

Sponsor(s): SPIE
 DT Conference Article; Journal
 TC Experimental
 CY United States
 LA English

L7 ANSWER 3 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 1997:5611672 INSPEC DN B9708-2550G-008
 TI Impact of lens aberrations on optical lithography.
 AU Brunner, T.A. (Microelectron. Div., IBM Corp., East Fishkill, NY, USA)
 SO IBM Journal of Research and Development (Jan.-March 1997) vol.41, no.1-2, p.57-67. 18 refs.
 Published by: IBM
 Price: CCCC 0018-8646/97/\$5.00
 CODEN: IBMJAE ISSN: 0018-8646
 SICI: 0018-8646(199701/03)41:1/2L:57:ILAO;1-N

DT Journal
 TC Theoretical
 CY United States
 LA English

L7 ANSWER 4 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 1996:5426662 INSPEC DN B9701-2550G-005; C9701-7410D-002
 TI Improvement of **resist pattern** fidelity with partial attenuated **phase shift mask**.
 AU Yasuzato, T.; Ishida, S.; Kasama, K. (VLSI Dev. Div., NEC Corp., Sagamihara, Japan)
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1996) vol.2726, p.496-507. 12 refs.
 Published by: SPIE-Int. Soc. Opt. Eng
 Price: CCCC 0 8194 2102 2/96/\$6.00
 CODEN: PSISDG ISSN: 0277-786X
 SICI: 0277-786X(1996)2726L:496:IRPF;1-Q
 Conference: Optical Microlithography IX. Santa Clara, CA, USA, 13-15 March

1996
 Sponsor(s): SPIE
 DT Conference Article; Journal
 TC Practical; Theoretical; Experimental
 CY United States
 LA English

L7 ANSWER 5 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 1995:5082029 INSPEC DN B9512-2550G-016
 TI A study of optical proximity effects using off-axis illumination with attenuated **phase shift mask**.
 AU Ahn, C.-N.; Baik, K.-H.; Lee, Y.-S.; Kim, H.-E.; Hur, I.-B.; Kim, Y.-S.; Kim, J.-H.; Choi, S.-H. (Semicond. R. & D. Labs., Hyundai Electron. Ind. Co. Ltd., Kyungki-do, South Korea)
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1995) vol.2440, p.222-39. 7 refs.
 Price: CCCC 0 8194 1788 2/95/\$6.00
 CODEN: PSISDG ISSN: 0277-786X
 Conference: Optical/Laser Microlithography VII. Santa Clara, CA, USA, 22-24 Feb 1995
 Sponsor(s): SPIE
 DT Conference Article; Journal
 TC Practical; Theoretical; Experimental
 CY United States
 LA English

L7 ANSWER 6 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 1995:4968479 INSPEC DN B9507-2550G-035
 TI Poly(cyclohexyl 2-cyanoacrylate-co-ethoxyethyl 2-cyanoacrylate) as a positive tone electron beam resist for **phase-shift mask** fabrication.
 AU Tamura, A.; Yonezawa, M. (Electron. Res. Lab., Toppan Printing Co. Ltd., Saitama, Japan); Sato, M.; Okuyama, T.
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1994) vol.2254, p.228-36. 4 refs.
 Price: CCCC 0 8194 1563 4/94/\$6.00
 CODEN: PSISDG ISSN: 0277-786X
 Conference: Photomask and X-Ray Mask Technology. Kanagawa, Japan, 22 April 1994
 Sponsor(s): SPIE; BACUS
 DT Conference Article; Journal
 TC Practical; Experimental
 CY United States
 LA English

L7 ANSWER 7 OF 7 INSPEC (C) 2003 IEE on STN

Full Text

AN 1992:4311819 INSPEC DN B9302-2550G-046
 TI Resolution improvement with annular illumination.
 AU Tounai, K.; Tanabe, H.; Nozue, H.; Kasama, K. (VLSI Dev. Div., NEC Corp., Kanagawa, Japan)
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1992) vol.1674, pt.2, p.753-64. 5 refs.
 Price: CCCC 0 8194 0829 8/92/\$4.00
 CODEN: PSISDG ISSN: 0277-786X
 Conference: Optical/Laser Microlithography V. San Jose, CA, USA, 11-13 March 1992
 Sponsor(s): SPIE
 DT Conference Article; Journal
 TC Practical; Experimental

CY United States
IA English

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